Computational analysis of physical and chemically assisted physical sputtering in plasma-facing components

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> Motivation

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Introduction

• Quantifying erosion and reflection from Beryllium (Be) surfaces, with pre-existing impurity content, using molecular dynamics (MD) simulations

Results

Methods

- Evaluating Chemically Assisted Physical Sputtering (CAPS) in Be surfaces, for different plasma particle characteristics
- Providing reliable data for Hydrogen (H) and Tritium (T), in addition to Deuterium (D) for further use in ERO2.0 simulations



Conclusion

Methods

Results

Conclusion

1. Surface Preparation

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• Be structures were initially loaded with H/D/T to set up a pre-existing concentration at different temperatures, based on the density profiles obtained at different surface temperatures through object kinetic Monte Carlo (OKMC) technique [1].

> How?

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- First, 5% of **Be** atoms were removed randomly.
- Then, at each depth range, a certain number of vacancies were selected and 5 ions were inserted in each (based on OKMC and DFT calculations) to obtain the initial distributions.
- Finally, the cells were equilibrated and the final density profiles were obtained.

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Methods

Conclusion

2. Time step

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- Running irradiation simulations with different values for the maximum time step (dt) and maximum distance each atom is allowed to move in one step (dx).
- Using no thermostat and electronic stopping to prevent any energy dissipation caused by them.
- The best option would be the combination that better preserves the energy of the system.

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3. Cell Size

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• To minimize the interaction between the incident ion and the boundary region, 3 different cell sizes were prepared and used for different impact energies and angles.



Results

Conclusion

Sputtering Yield

Introduction

• The figure represents the total sputtering yield of Be-D structure at 300K for normal incidence.

Methods

- Good agreement with the experimental values for Be with D present in the structure (light blue stars)
- Overall, no decreasing trend in the yield for impact energies higher than 50 eV





- [1] E. Safi et al., Journal of Physics D: Applied Physics (2017).
- [2] R. Behrisch and W. Eckstein, Springer (2007).
- [3] C. Björkas et al., New Journal of Physics (2009).
- [4] S. Shermukhamedov et al., Nuclear Fusion (2021).
- [5] D. Nishijima et al., Journal of Nuclear Materials (2009).

Methods

> Sputtering Yield

- Large difference between MD and SDTrimSP yields at low energies is observed.
- The agreement at high energies is very good.
- This emphasizes on the importance of CAPS at low energies.





[1] E. Safi et al., Journal of Physics D: Applied Physics (2017).

- [2] R. Behrisch and W. Eckstein, Springer (2007).
- [3] C. Björkas et al., New Journal of Physics (2009).
- [4] S. Shermukhamedov et al., Nuclear Fusion (2021).
- [5] D. Nishijima et al., Journal of Nuclear Materials (2009).

Sputtering Yield

- H isotope
 - > In general, increasing the isotope mass will result in an increase in the sputtering yield due to a more efficient momentum transfer.
 - > Good agreement is observed with SDTrimSP results for all isotopes at higher impact energies.



Sputtering Yield

• Impact angle

- Increasing the impact angle from 0° to ~
 65° increases the sputtering yield.
- Further increments will result in a sharp decrease of the sputtering yield.
- Same behavior is observed for all isotopes, with only difference being the magnitude of the yield.
- Compared to SDTrimSP data we get higher yield values, with the maxima at lower angles followed by a sharper decrease.

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Methods

> Sputtering Yield

Introduction

- Surface temperature
 - > In general, a lower sputtering threshold is observed at higher surface temperatures.



Conclusion



- > CAPS
 - Impact energy
 - > The higher the impact energy, the lower the probability of CAPS will be.
 - > Same trend has been observed for all isotopes.





> CAPS

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• H isotope

- Moving from the lightest (H) to the heaviest isotope (T) the probability of CAPS decreases strongly.
- This could be resulted from a longer interaction time between H and Be and a less momentum transfer due to a larger mass difference.

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CAPS \succ

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- Surface temperature
 - ۶ **H:** lower CAPS contribution at elevated surface temperatures.
 - **D**/**T**: increased CAPS contribution at low energies and decreased contribution at high energies. ۶



Conclusion

> Reflection



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> Reflection



15

> Reflection





> ERO2.0

• The MD data have been implemented in ERO2.0 and tests are being performed to benchmark the results.



The size of the cells and the time step significantly influence the simulations and must be chosen with care.

Findings show a significant reliance of the sputtering yield, CAPS, and reflection on the characteristics of the plasma particle.

MD results are in strong agreement with SDTrimSP results for sputtering yield at high impact energies.

Nonetheless, inability of SDTrimSP to incorporate CAPS highlights the essential role of MD, especially at lower energy levels.

Thanks for your attention!

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